

## Electronic Patent Application Fee Transmittal

<b>Application Number:</b>	10092795			
<b>Filing Date:</b>	06-Mar-2002			
<b>Title of Invention:</b>	METHOD OF PLASMA ETCHING OF HIGH-K DIELECTRIC MATERIALS WITH HIGH SELECTIVITY TO UNDERLYING LAYERS			
<b>First Named Inventor/Applicant Name:</b>	Padmapani C. Nallan			
<b>Filer:</b>	Keith Patrick Taboada			
<b>Attorney Docket Number:</b>	7017/ETCH/CONE			
Filed as Large Entity				
<b>Utility      Filing Fees</b>				
<b>Description</b>	<b>Fee Code</b>	<b>Quantity</b>	<b>Amount</b>	<b>Sub-Total in USD(\$)</b>
<b>Basic Filing:</b>				
<b>Pages:</b>				
<b>Claims:</b>				
<b>Miscellaneous-Filing:</b>				
<b>Petition:</b>				
<b>Patent-Appeals-and-Interference:</b>				
<b>Post-Allowance-and-Post-Issuance:</b>				
Certificate of correction	1811	1	100	100
<b>Extension-of-Time:</b>				

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Miscellaneous:				
Total in USD (\$)				100